

Lithography Performance Improvement.

Equipment Manufactures Meet Technological Demands.

Lithography equipment manufactures employ the greatest minds in the engineering world, designing cutting edge technology to meet the increasing demands of nanotechnology manufactures.



Two primary contenders remain at the forefront of the fast paced technology sector; ASML and Nikon.

These two companies strive to satisfy the industry requirement for improved equipment performance, by integrating sophisticated metrology and analytics software that enables high performance tuning of the lithography machine.



With portfolios of software capabilities called Lithography Equipment Engineering Systems (LEES), and Holistic Lithography, the top tool vendors are achieving great success in satisfying their customers and stretching the boundaries of nanotechnology.

Performance Improvement. More than technology.

Driving the performance improvement initiatives are consortiums made up of chip manufactures from across the semiconductor industry. Two such consortiums are SEMATECH and ISMI.



Carefully outlined improvement requests, are articulated in international symposiums. LEES and Holistic Litho are two successful examples of technological efforts to address the articulated needs of the semiconductor community.



Accelerating Manufacturing Productivity

The articulated needs of the consortium, extends beyond technology, beyond Overall Equipment Effectiveness (OEE), and into what is called Overall Labor Effectiveness (OLE).

OLE is a measure of how well staff interface and leverage the technology at their disposal, and how effectively they create product using the technology.

Leverage Intellectual Property . Maximize OLE.

Using the latest learning technologies and strategies, Knowledge Broker Inc creates web based, Performance Improvement solutions for your enterprise.



CERTIFIED CONFIDENCE.

Based upon SEMI standard E150, KBI designs simulators that enable your staff to learn sophisticated software like ASML's Tachyon SMO, or Nikon's Technology Aberration Optimization TAO.



KBI contends that success will not only be in the integration of cutting edge technology, but how well the labor components are prepared to perform using that technology.

Provide your staff, reusable, cost effective web based learning opportunities now, and leverage the intellectual power of your enterprise.

Educate and Simulate on lithography topics like:

- [Tachyon SMO](#)
- [Tech Aberration Optimization TAO](#)
- [FlexRay](#)
- [Litho Tuner](#)
- [Infrared Aberration Control – IAC](#)
- [BaseLiner](#)
- [OLEV Overlay Evaluation Program](#)
- [YieldStar](#)
- [Optimized Dose Control – ODC](#)
- [Grid Compensation for Matching](#)

Improve your OLE, and provide your customers the confidence they need to continue to invest in your vision.

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